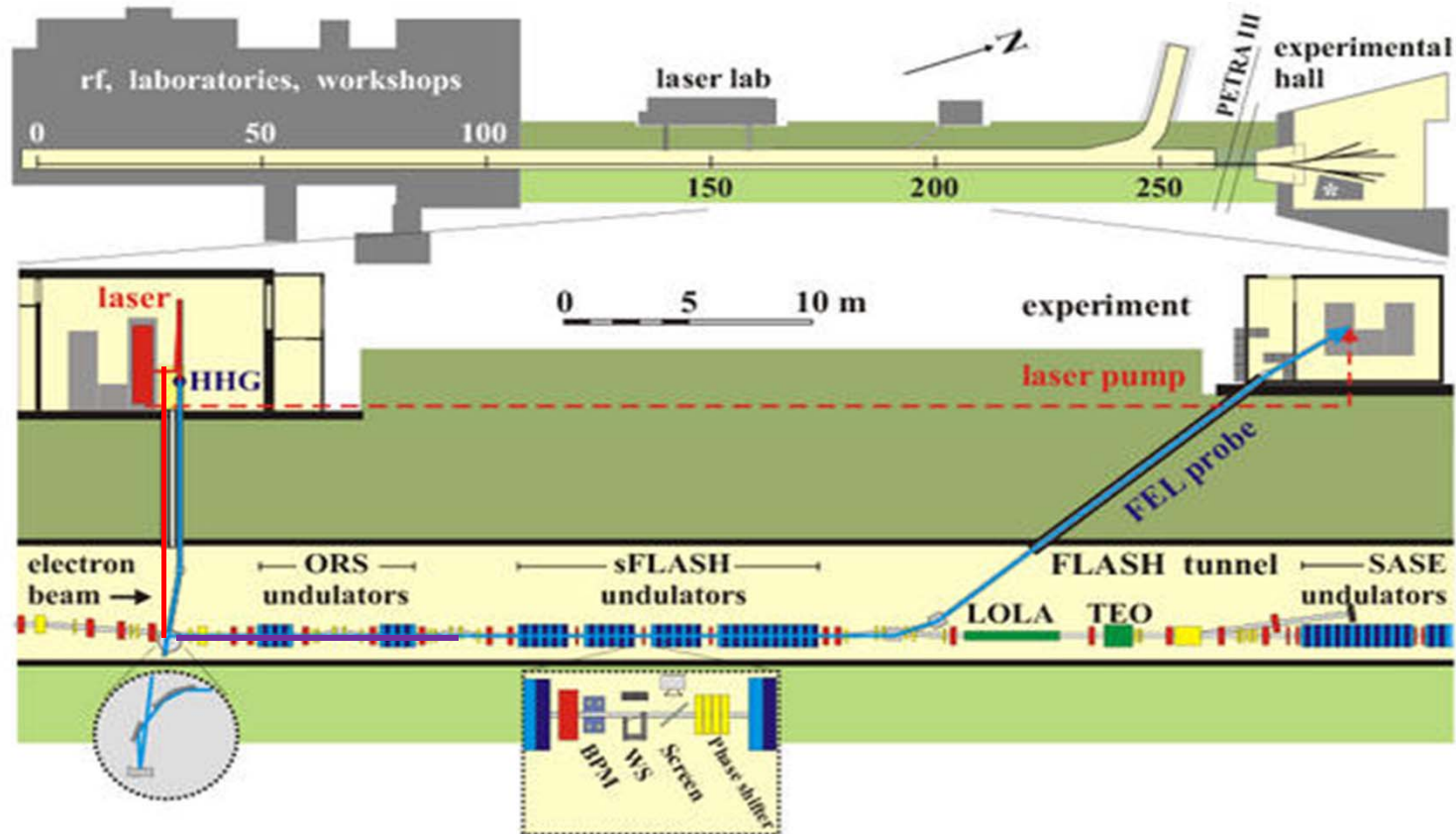


EEHG at FLASH 2012 and beyond

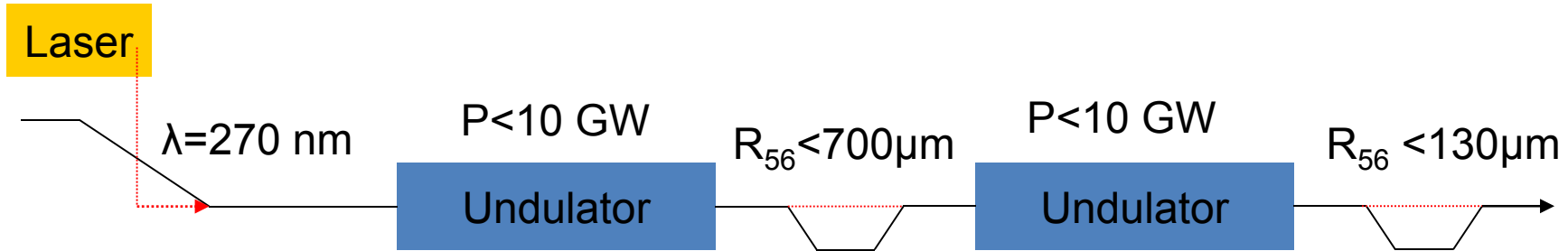
Kirsten Hacker*, Shaukat Khan, **TU Dortmund**
Gergana Angelova Hamberg, Volker Ziemann, **Uppsala University**
Peter Salen, Peter Van der Meulen, **University of Stockholm**
Armin Azima, **University of Hamburg**
Holger Schlarb, **DESY**

ORS and sFLASH

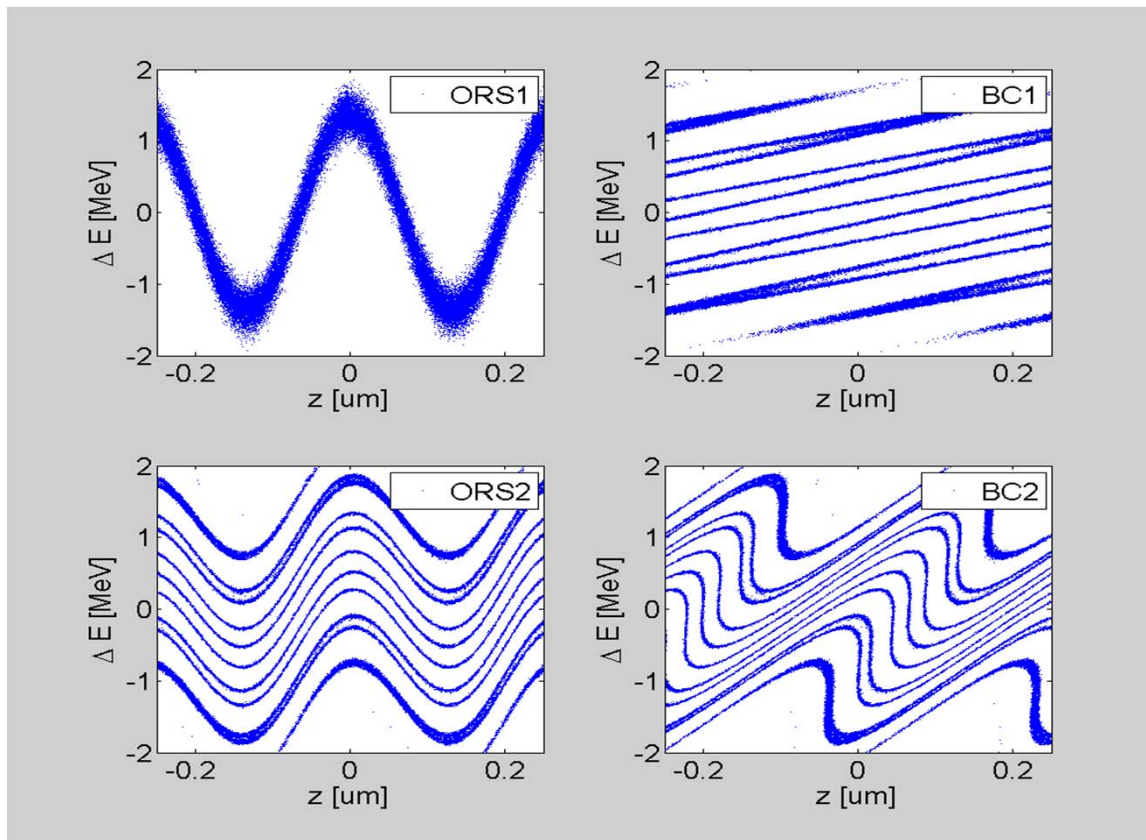


- sFLASH EEHG 14 nm
- SASE HHG 4.7 nm
- sFLASH HHG 38.5 nm simple commissioning

Echo-seeding



$$\Delta E/E < 4 \cdot 10^{-3}$$



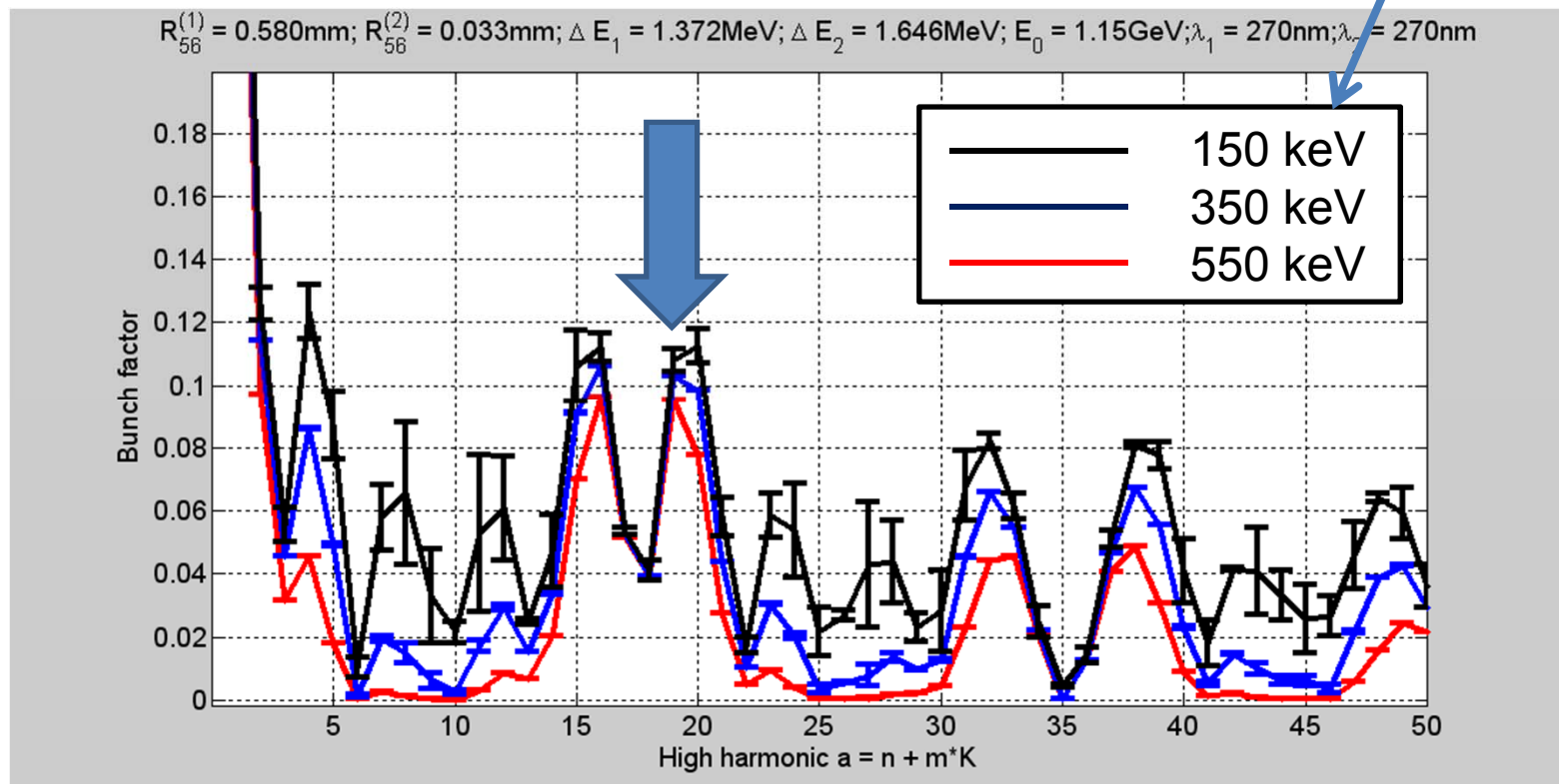
EEHG at 14 nm

Larger laser power => larger energy spread

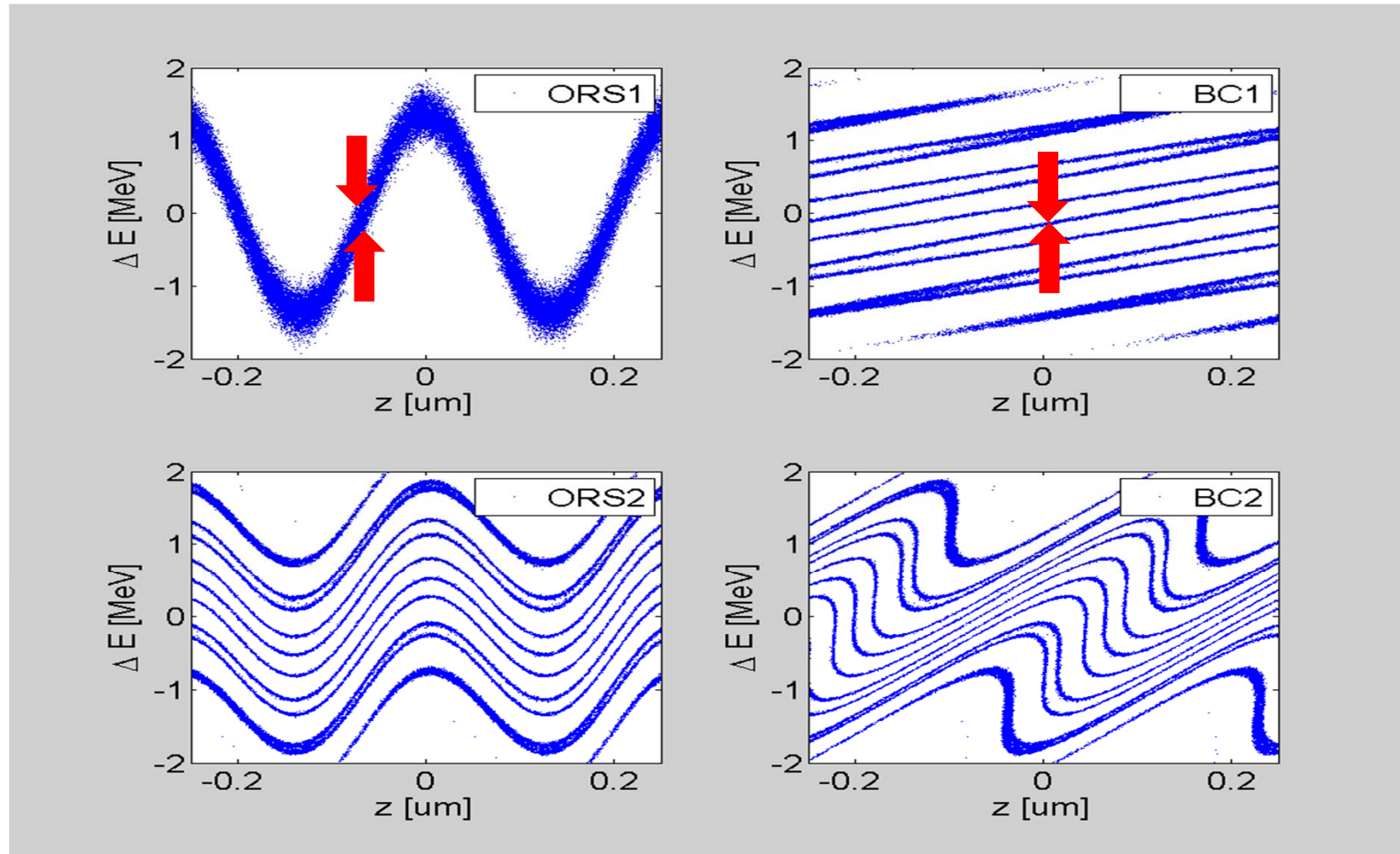
Lower uncorrelated energy spread sensitivity

Lower energy fluctuation sensitivity

Uncorrelated energy spread

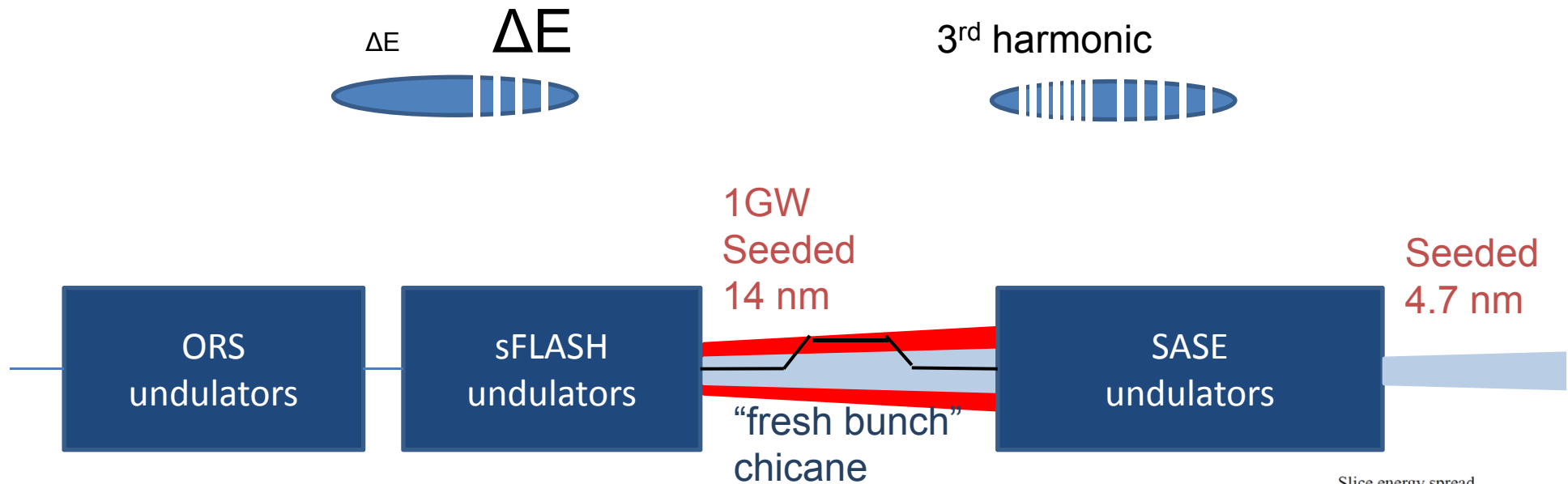


Liouville => effective cooling

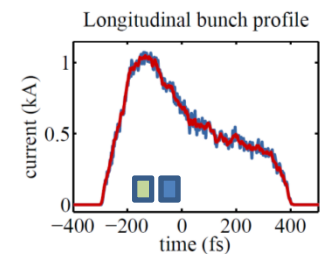
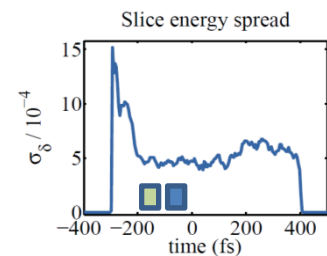
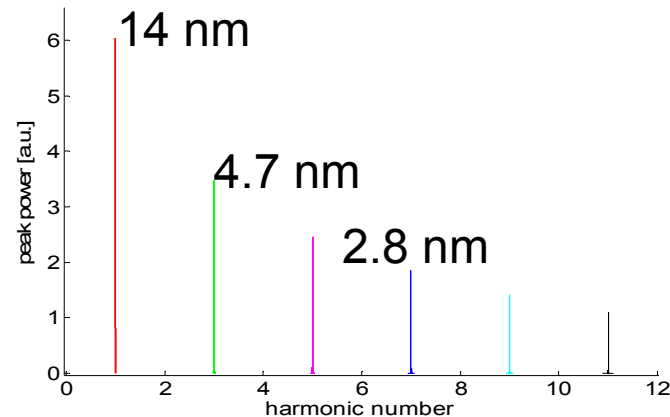


Advantage of EEHG over HGHG

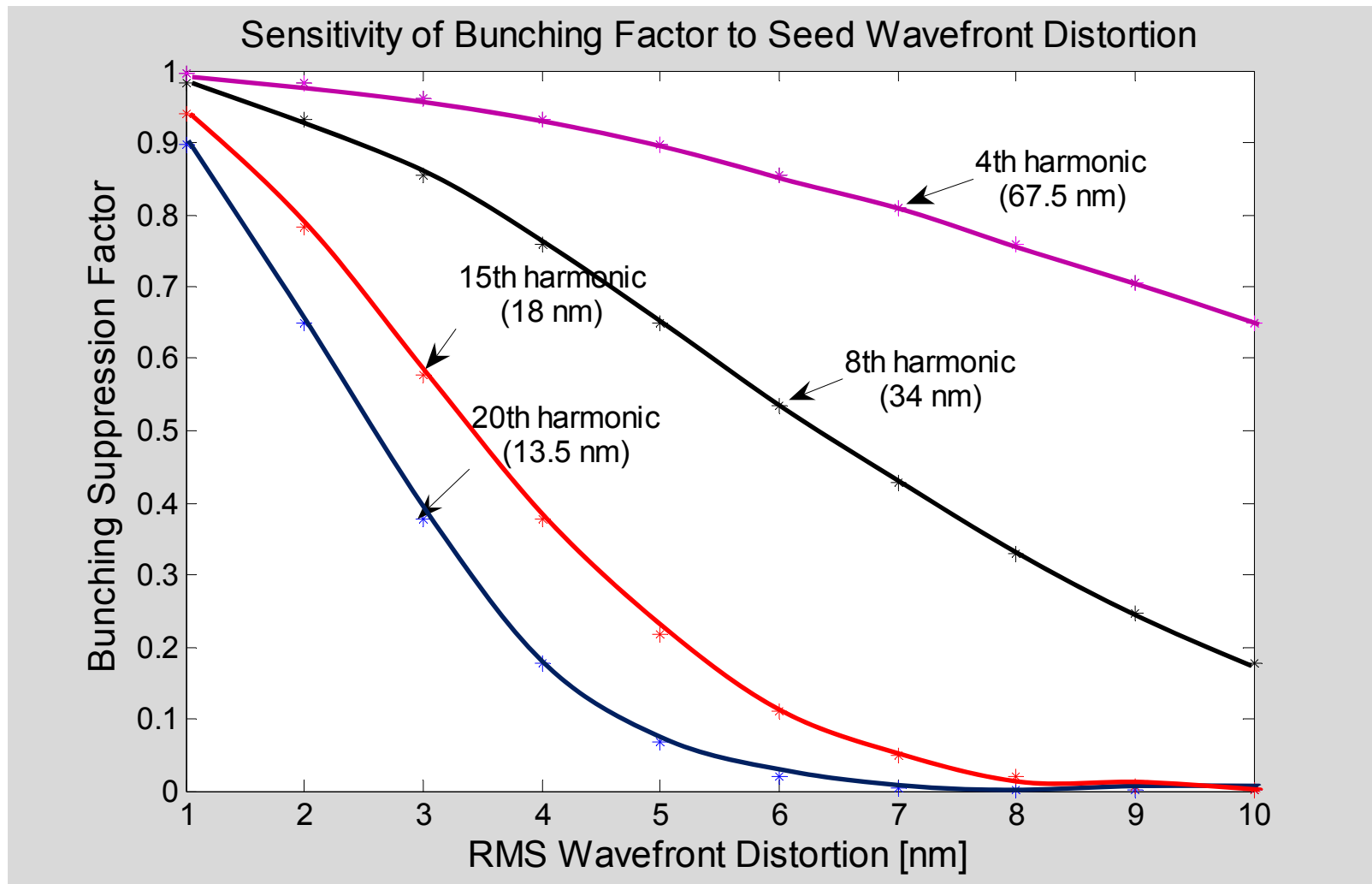
Final Destination: EEHG + HGHG



Fresh bunch technique
OR
Super-radiant regime

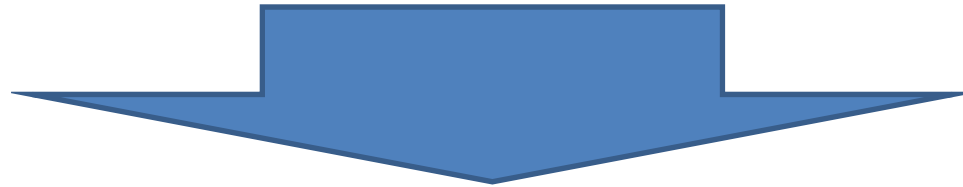


Wavefront distortions: biggest problem for higher harmonics



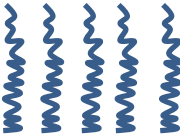
HGHG and laser wavefront

- By reaching saturation in sFLASH undulators, the wavefront is ****cleaned****

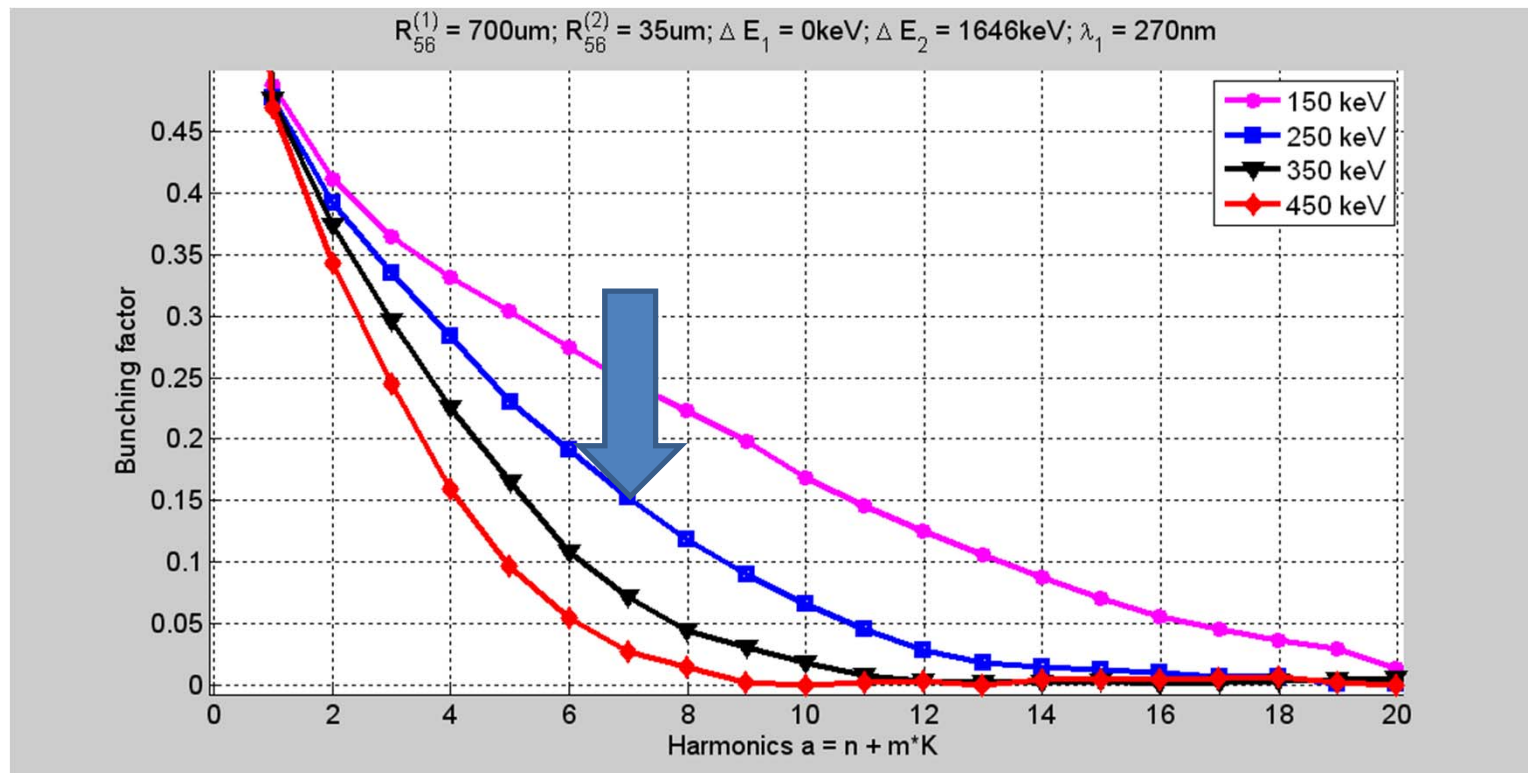
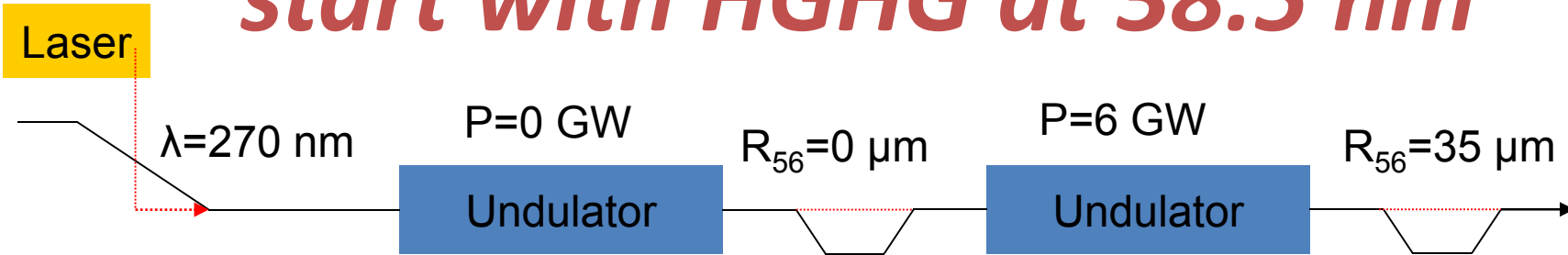


- If our laser wavefront quality is good enough for 14 nm, it is good enough for 4.7 nm

EEHG and laser wavefront

- Wavefront tilt: 
 - Adjust magnets prior to radiator
- Lower-order deformations: 
 - Adjust deformable mirror for 270 nm
- Higher-order deformations: 
 - Use flatter optics or add spatial filter

Commissioning strategy: start with HGHG at 38.5 nm



Commissioning strategy

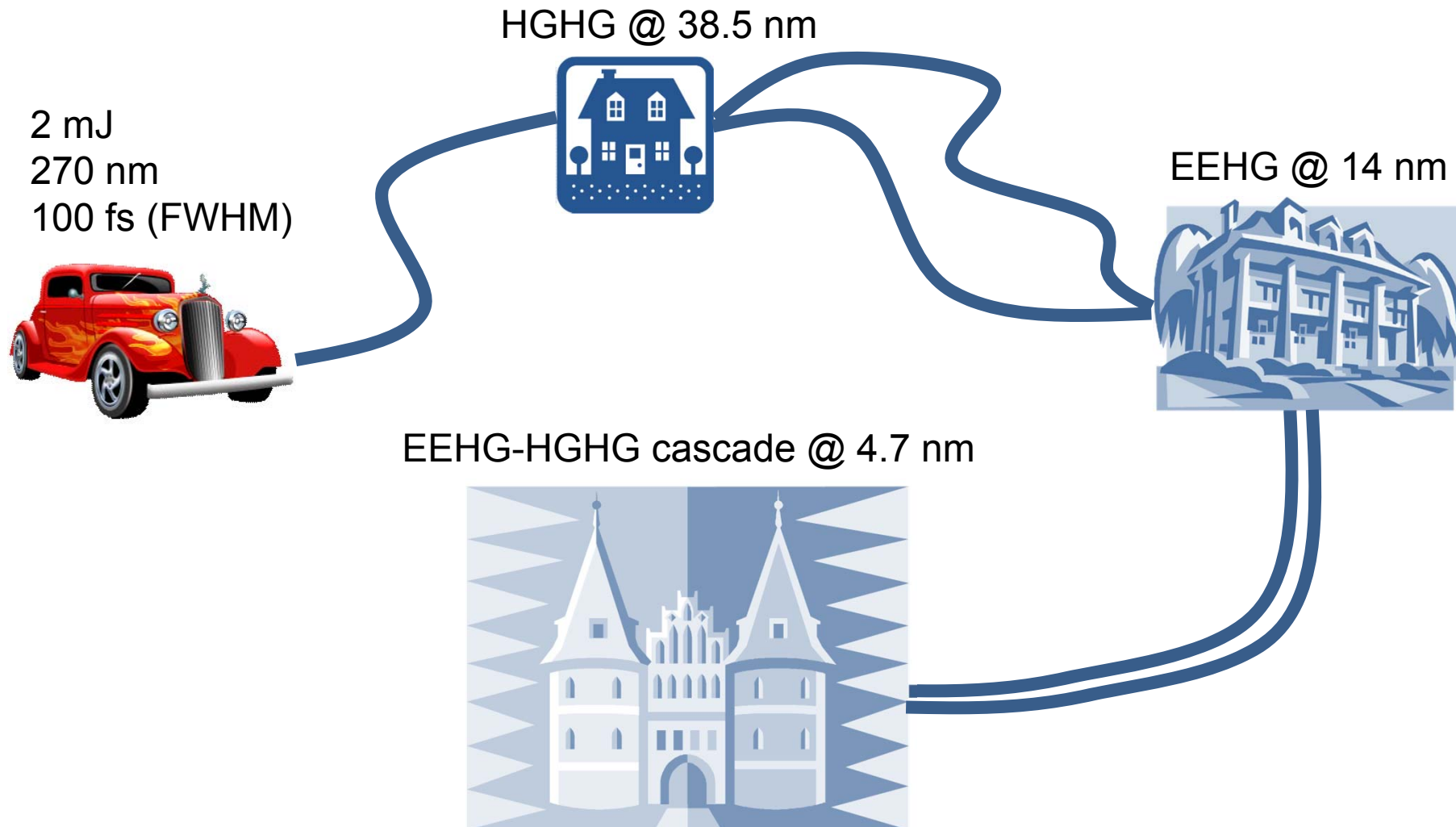
- We will only need a *few shifts of beam time* for calibrating our near and far-field laser beam position measurements against measurements conducted in the electron beam line with insertable screens.
- Regardless of the machine setup, we can generate a *parasitic EEHG program* which can use one bunch out of the bunch train
 - Requires ORS chicanes and undulators to be ON all of the time.

Summary

- We will start with an easy, already proven scheme and work our way towards seeding at 4.7 nm
- EEHG has some inherent advantages over other seeding techniques
 - Low energy spread sensitivity
 - Ease of removing effect of laser wavefront tilts
 - Easier to tune low-order wavefront distortions
 - Not as constrained in choice of harmonic
- This experiment can be conducted parasitically on an ongoing basis

Thank you for your time

Road map



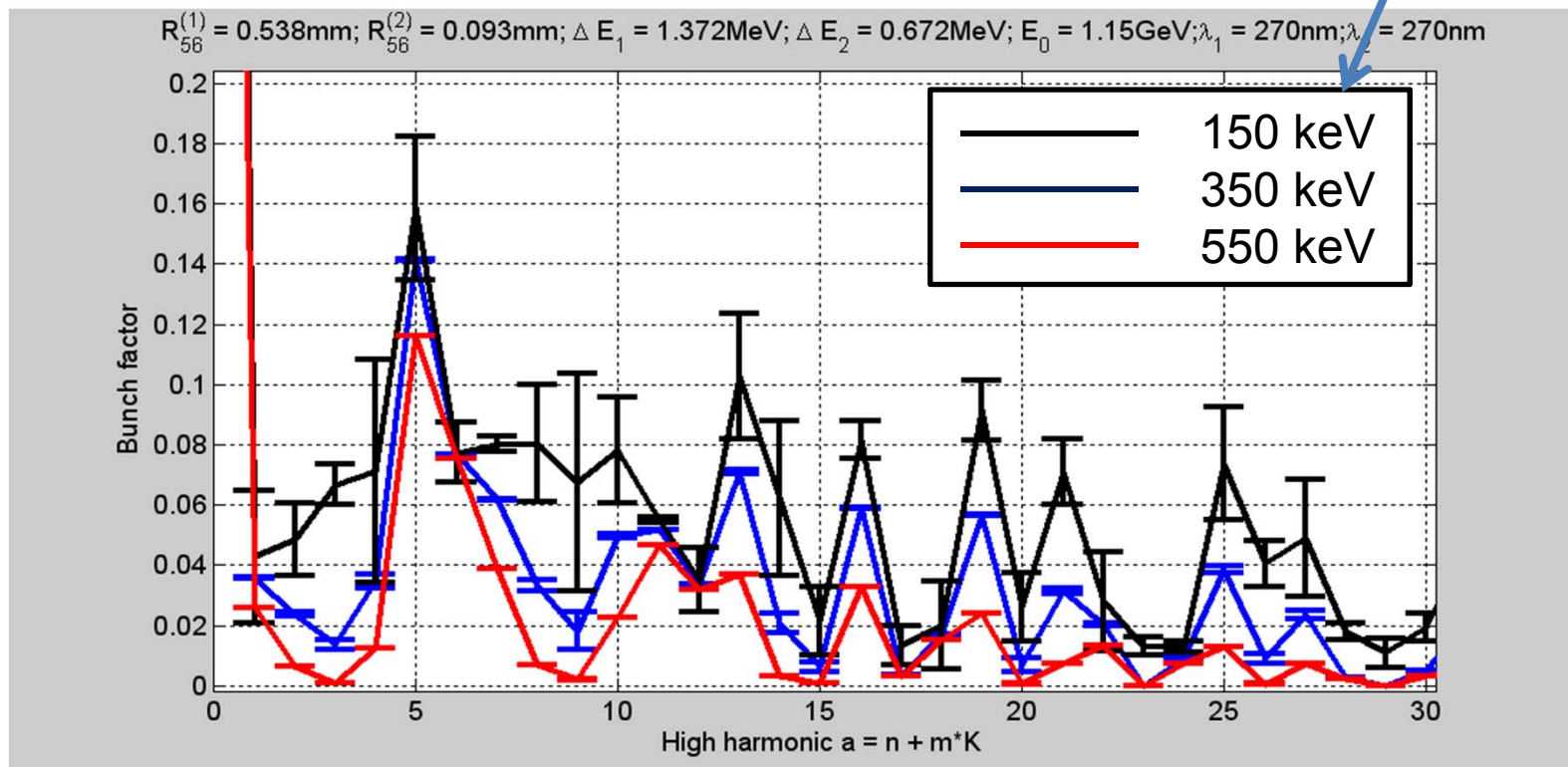
Route 2: hybrid EEHG-HGHG

Smaller laser power => smaller energy spread

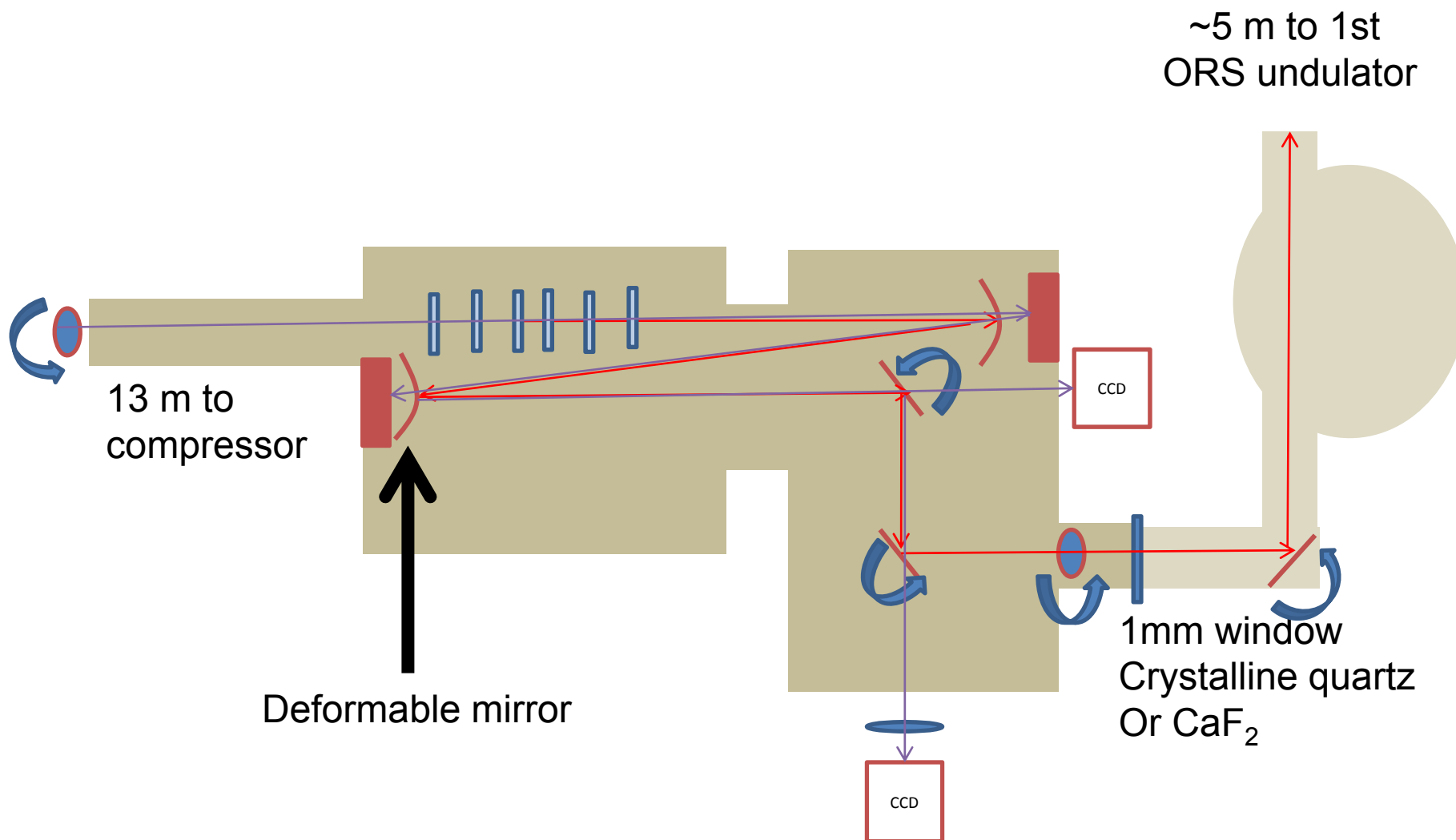
Higher uncorrelated energy spread sensitivity

Higher energy fluctuation sensitivity

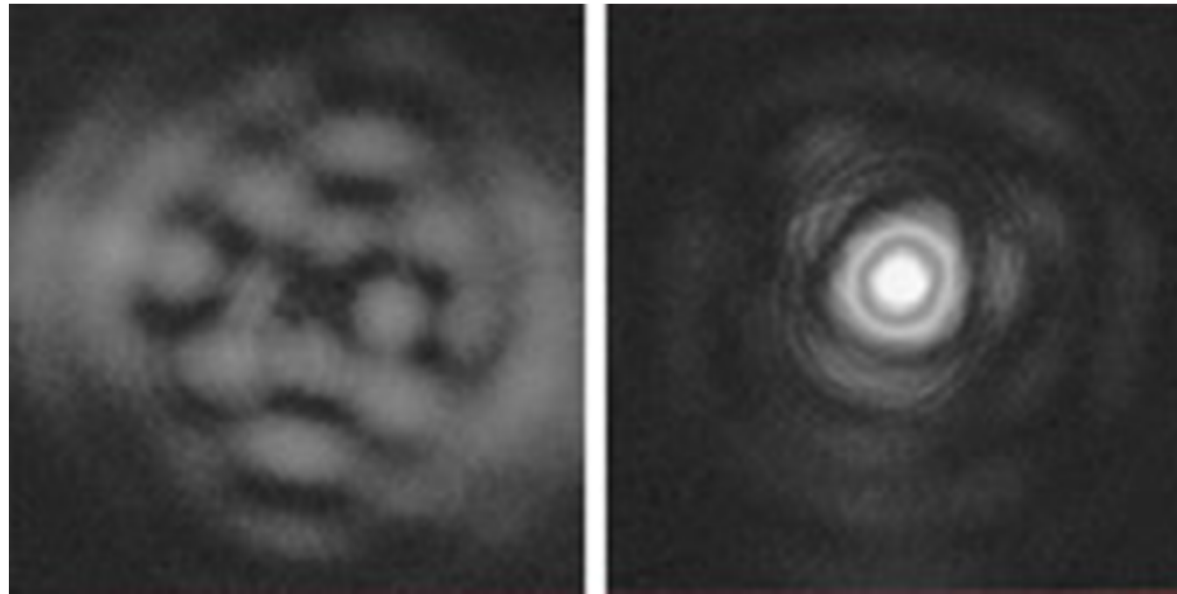
Uncorrelated energy spread



First iteration



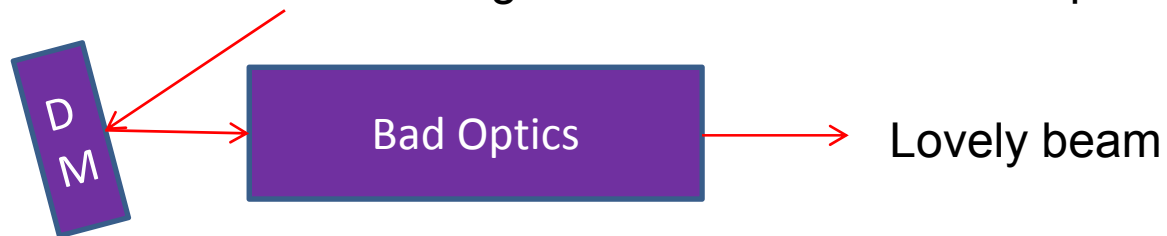
Laser Wavefront Control



Before

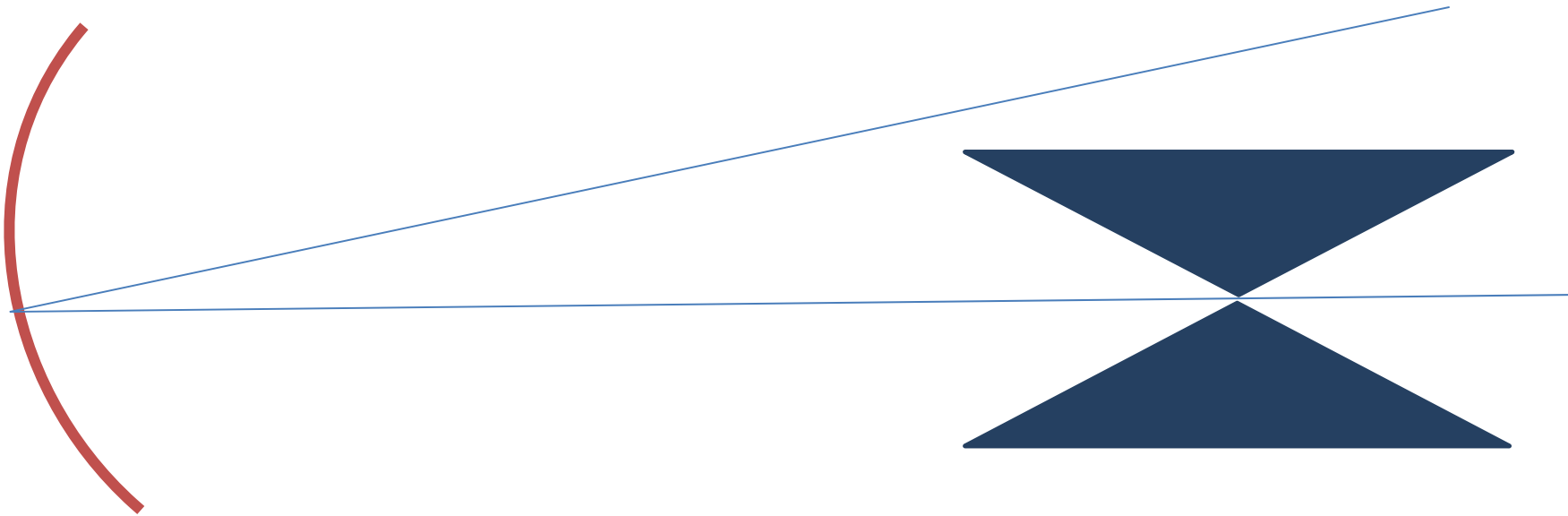
After

Large-scale distortions => Adaptive optics



Laser Wavefront Control

Microscopic distortions => Spatial filter



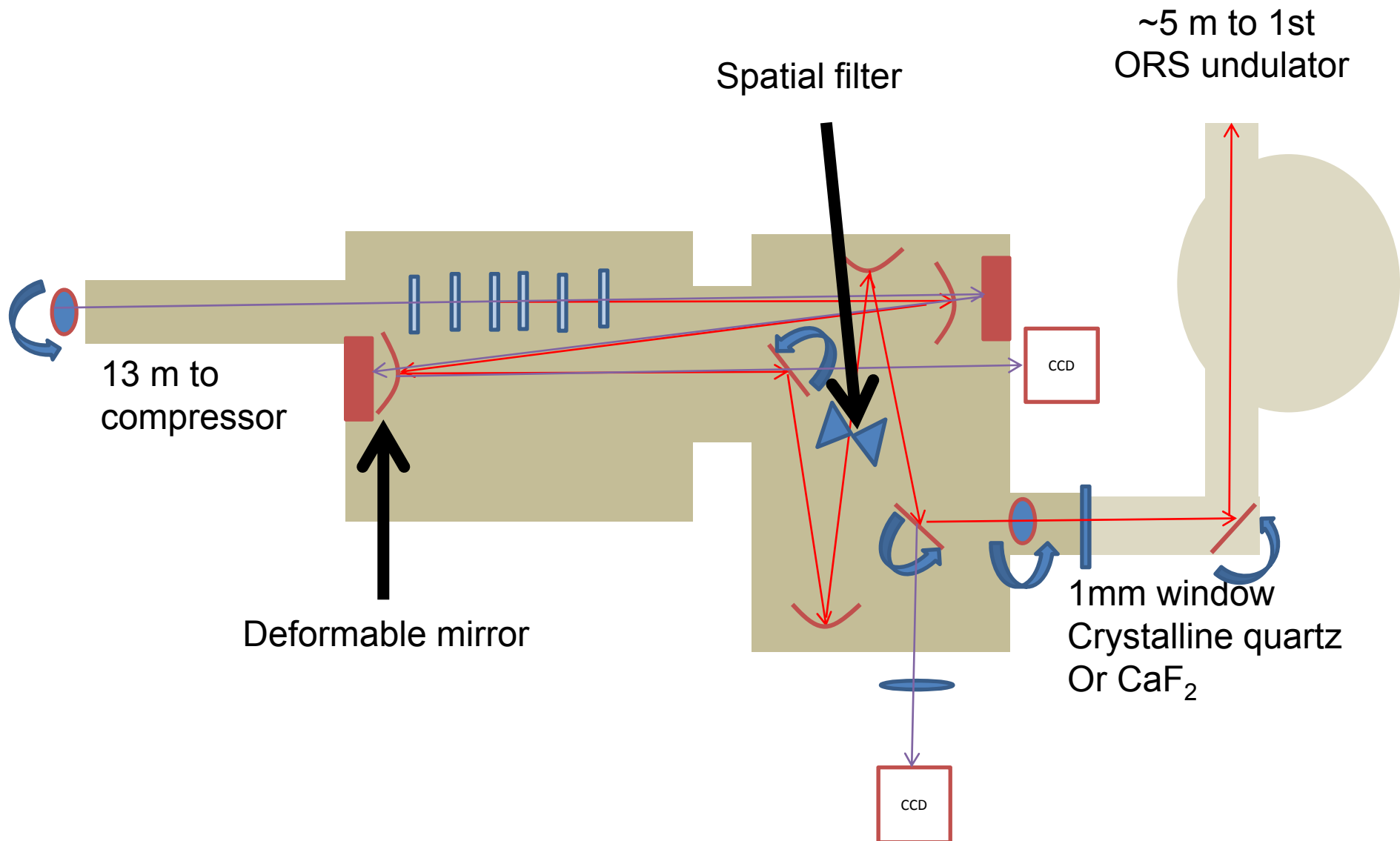
Dielectric conical filtering hole at diffraction limit

- 50% losses

- intensity jitter increases due to pointing jitter

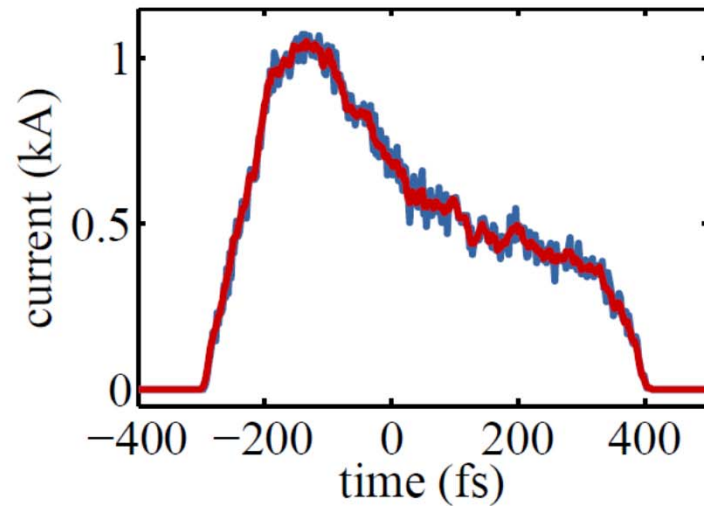
- pointing jitter -> fast steering feedback

Second iteration

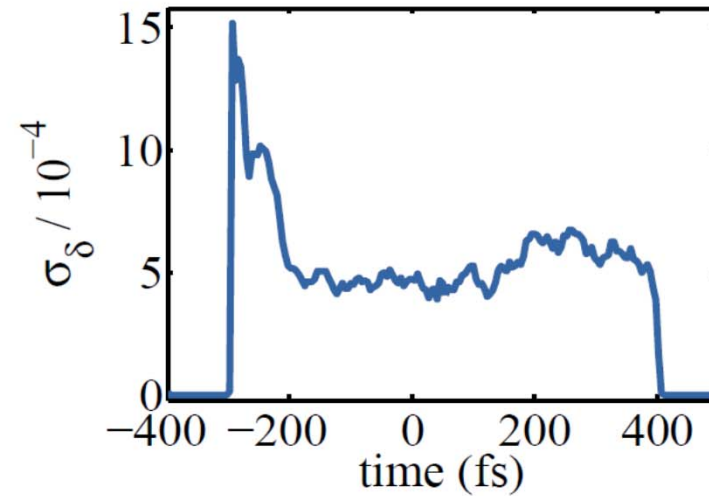


Electron beam

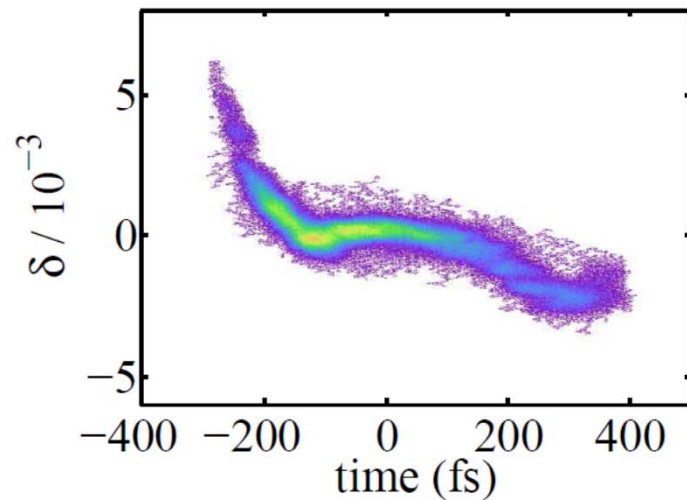
Longitudinal bunch profile



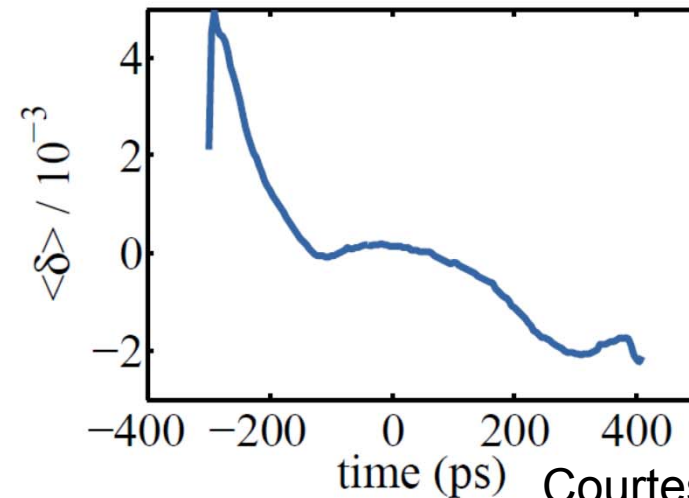
Slice energy spread



Longitudinal phase space

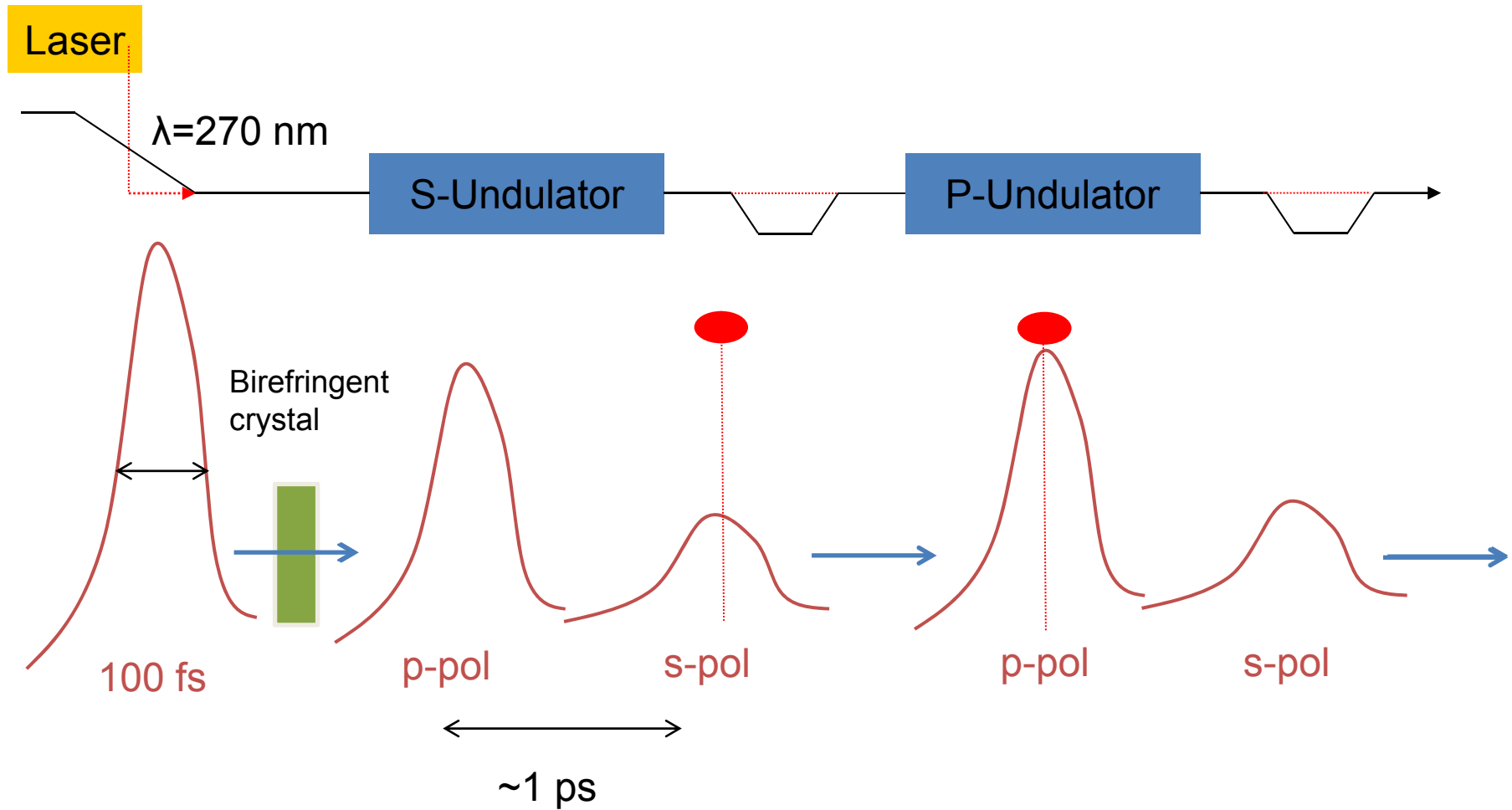


Mean slice energy

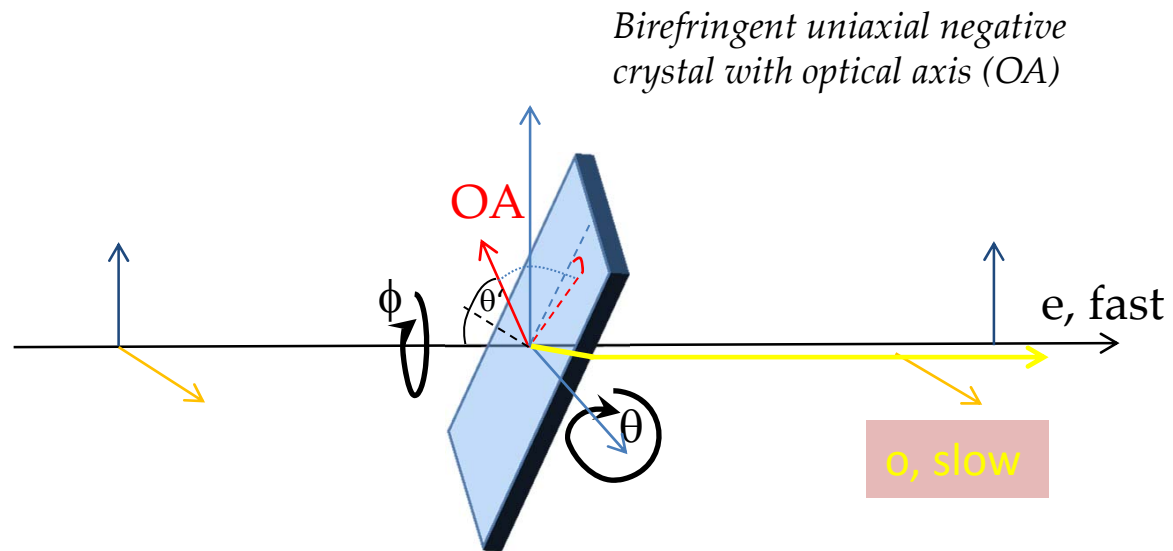


Courtesy C. Behrens

EEHG with one laser

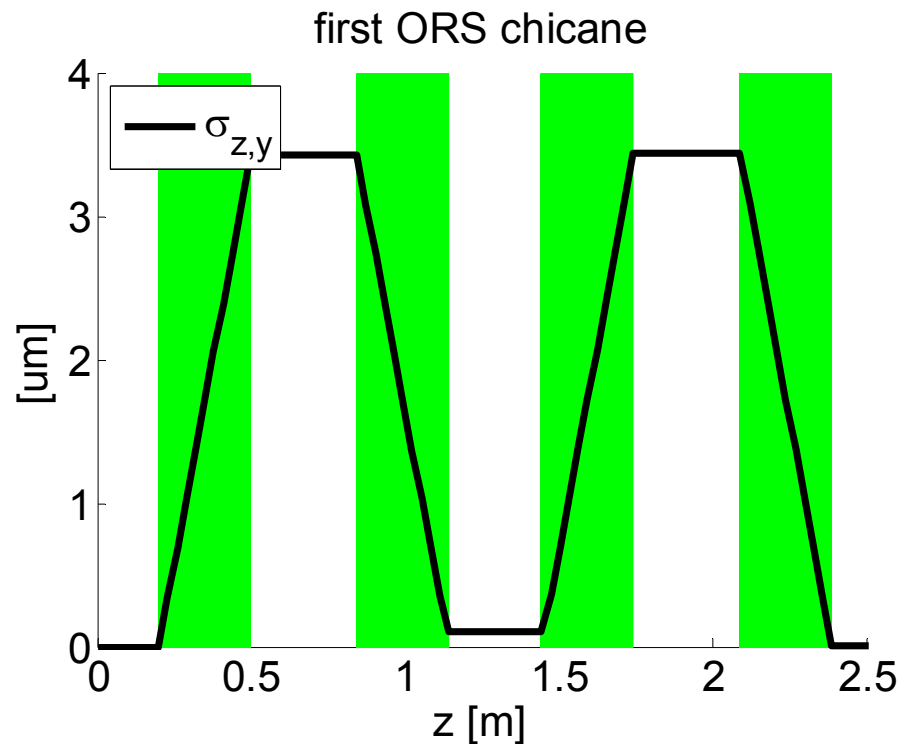


Laser Power Control

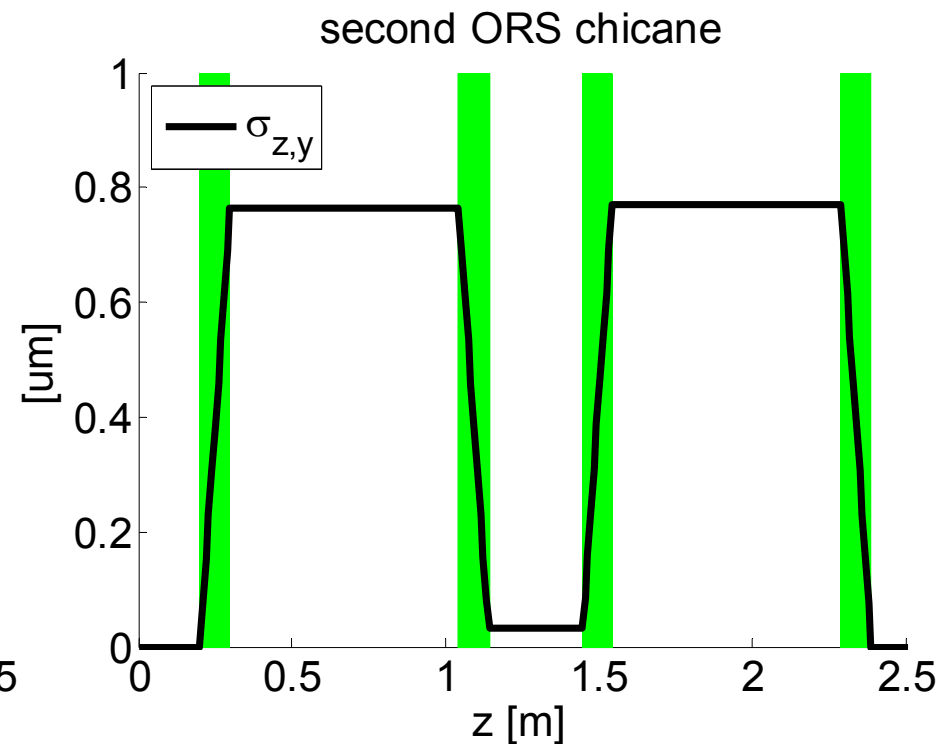


R_{53} & R_{54} smearing out spikes

$$\sigma_{z,y}^2 = R_{53}^2 \sigma_y^2 + R_{54}^2 \sigma_{y'}^2$$



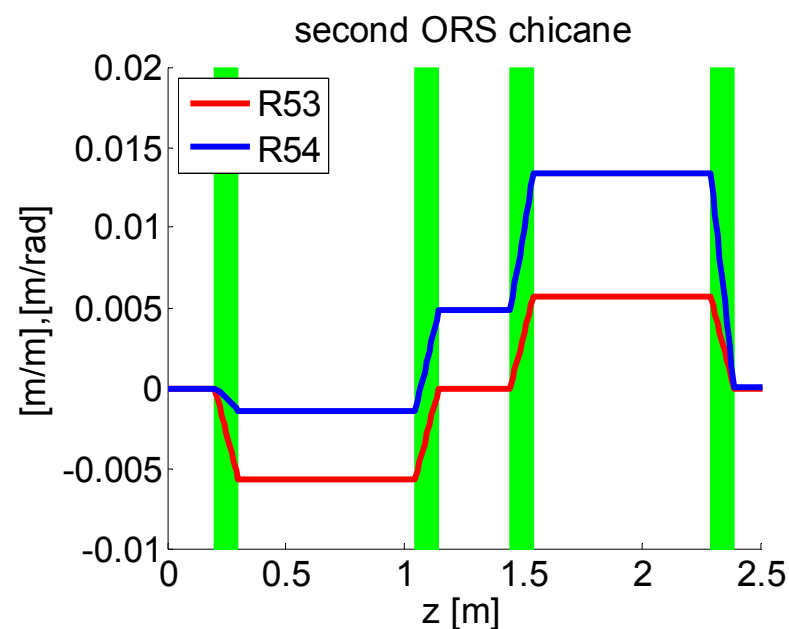
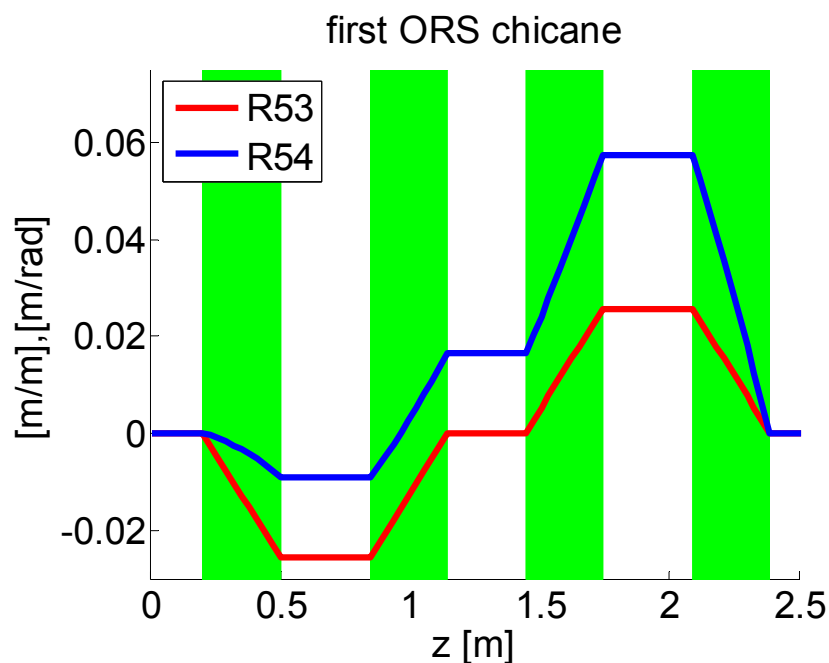
100 nm minimum



30 nm minimum

$$\sigma_{z,y} < \lambda_r/20$$

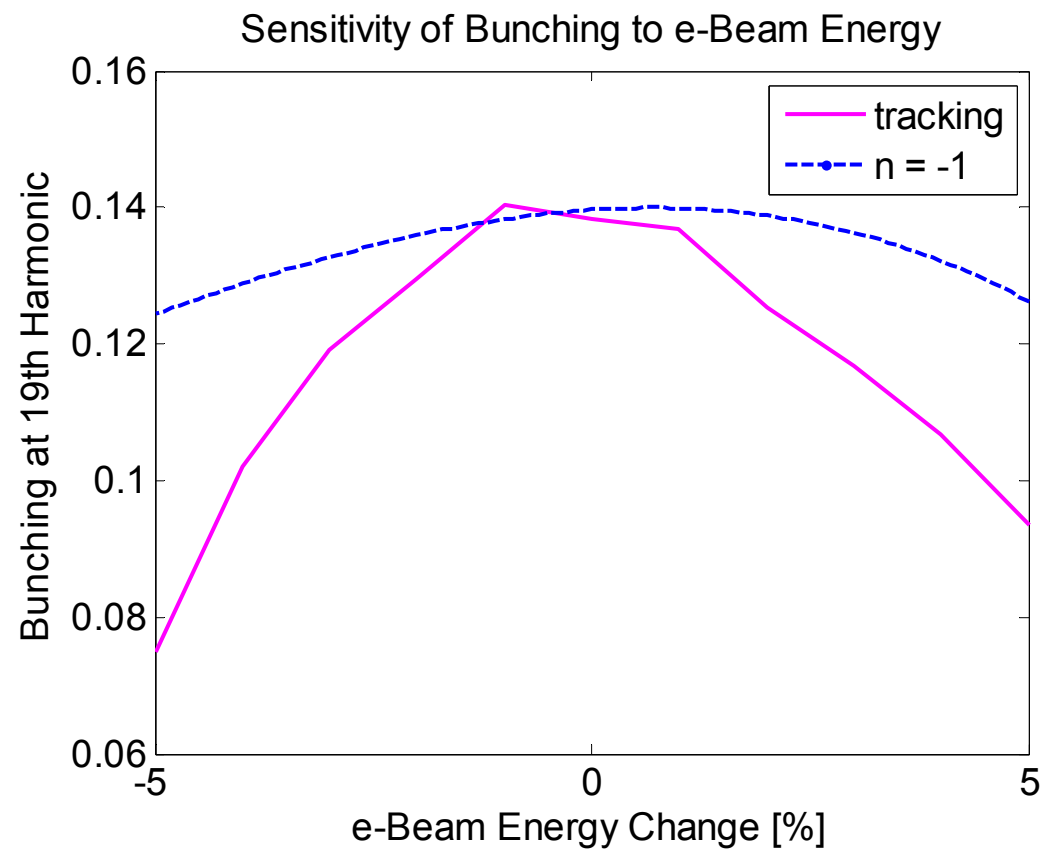
R_{53} & R_{54} leakage due to CSR



$$\sim \exp(k^2 R_{53}^2 \sigma_y^2 / 2)$$

- ⇒ Magnetic field of first chicane must be tuned to within 0.05%
- ⇒ Magnetic field of second chicane must be tuned to within 0.20%

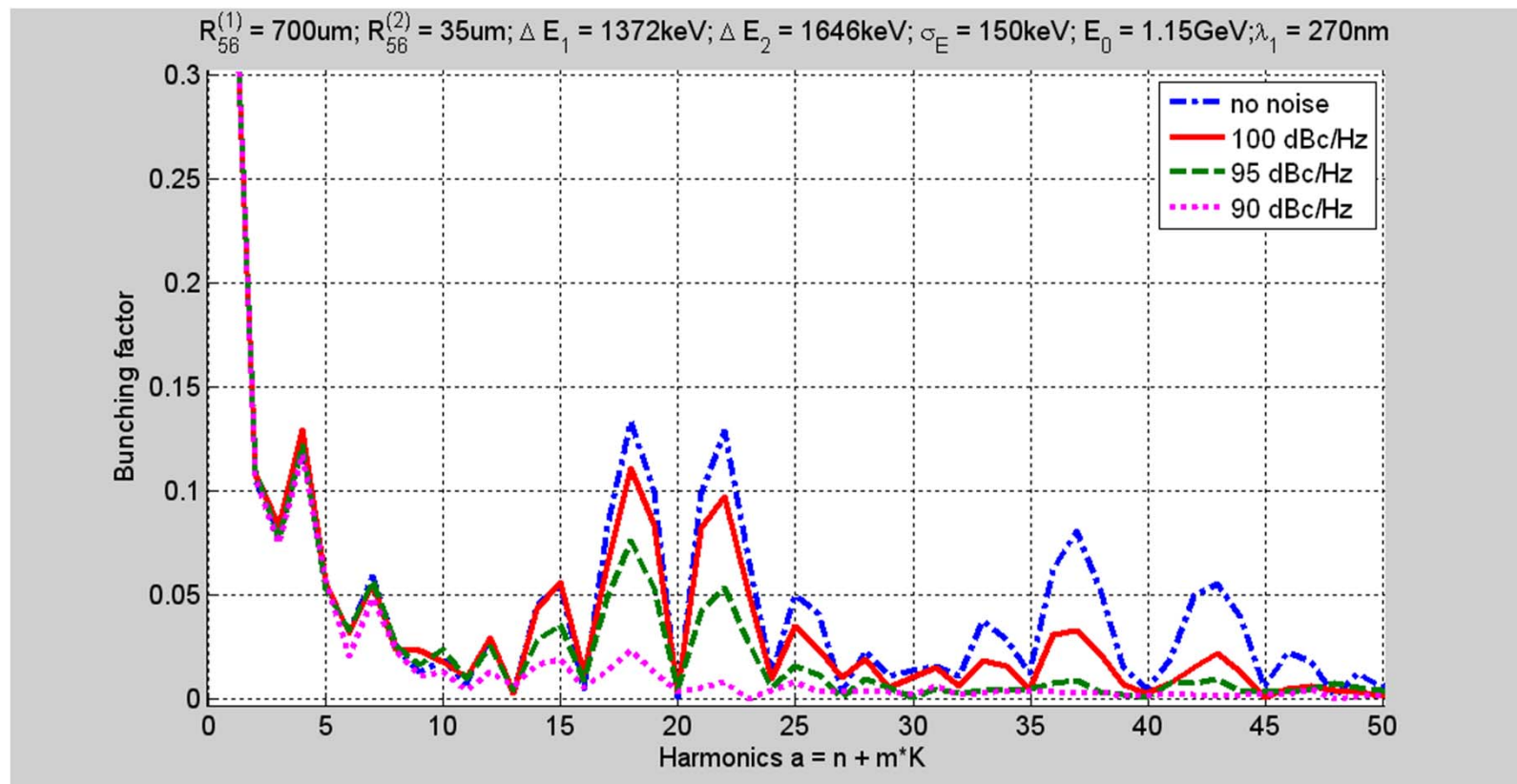
Beam Energy Sensitivity



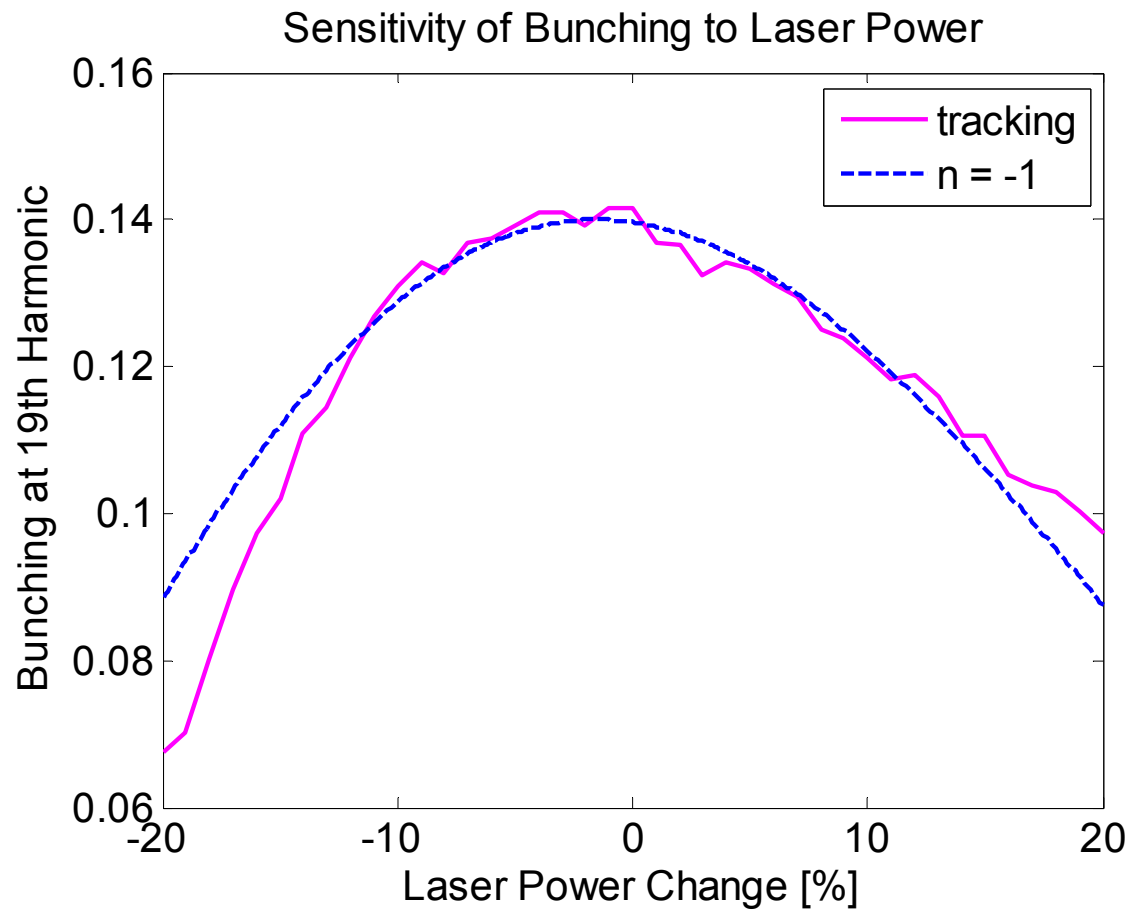
Phase Noise Sensitivity

All seeding schemes
Same rule?

$$\left(\frac{P_s}{P_n} \right)_{out} = \frac{1}{n^2} \left(\frac{P_s}{P_n} \right)_{in}$$



Laser Power Sensitivity



Incoming Microbunches

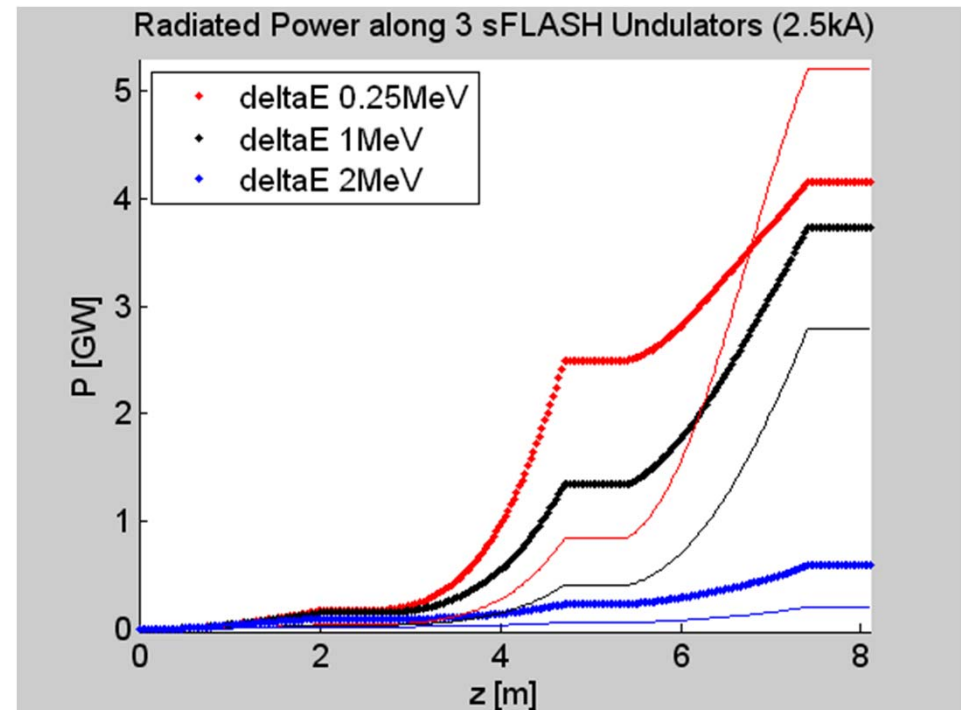
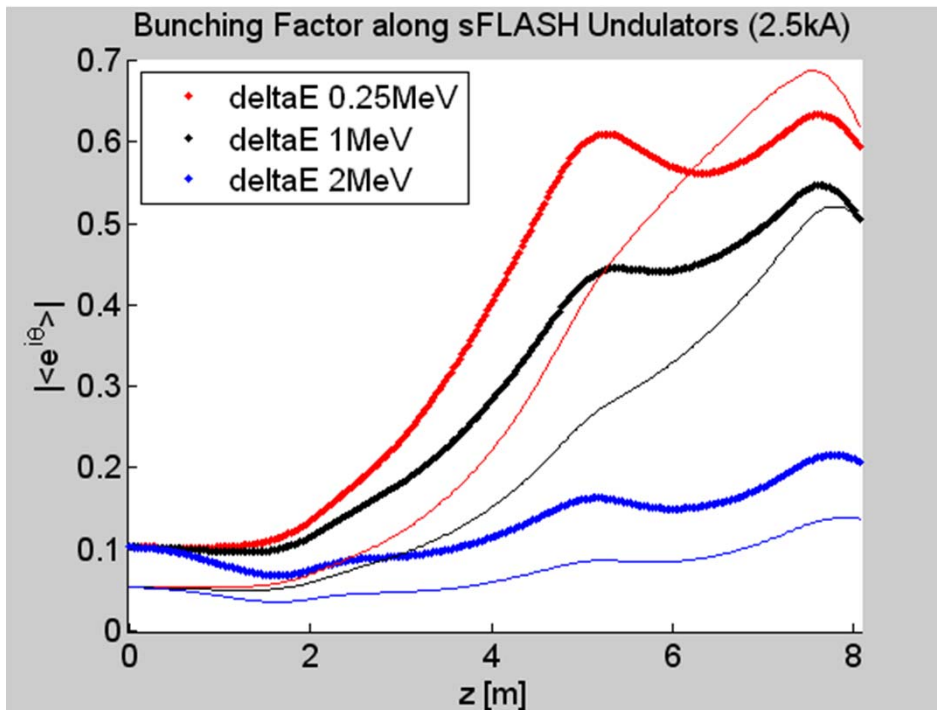
- Broadband spectrum <300 nm to 15 μm (measured)
- On-crest form factor ~ 0.01
- Off-crest form factor much higher
- ORS undulator amplifies wavelengths from incoming microbunching spectrum
- 800 nm MBI could be exacerbated in ORS section
- Constructive and destructive interference with EEHG modulation (varying from cycle-to-cycle)

Structures smaller than 600 nm are smeared out in dogleg
&
Sub-harmonics don't radiate on axis

GENESIS

Through the first 3 sFLASH undulators

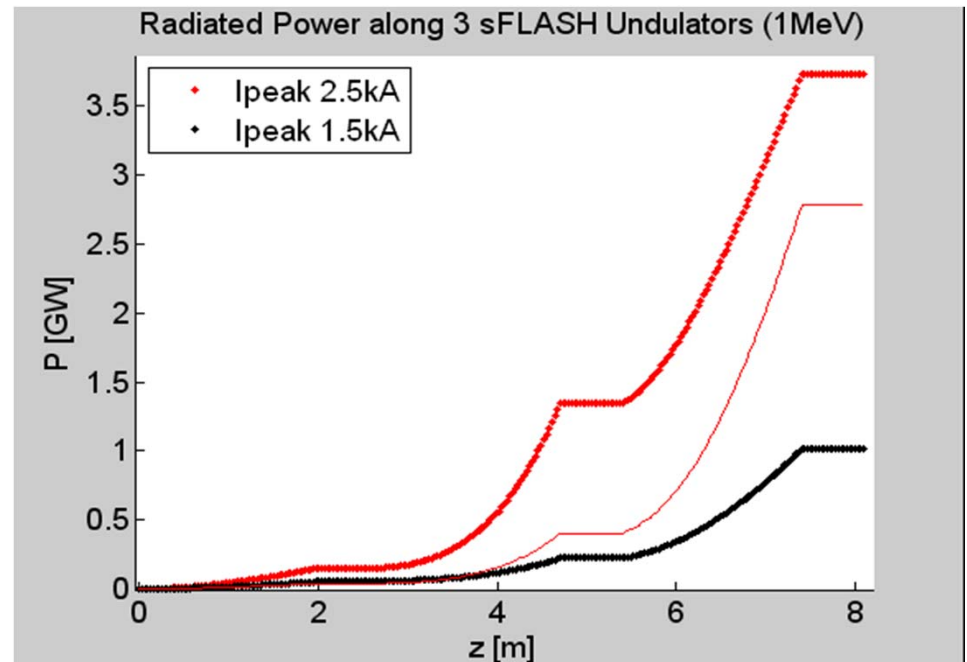
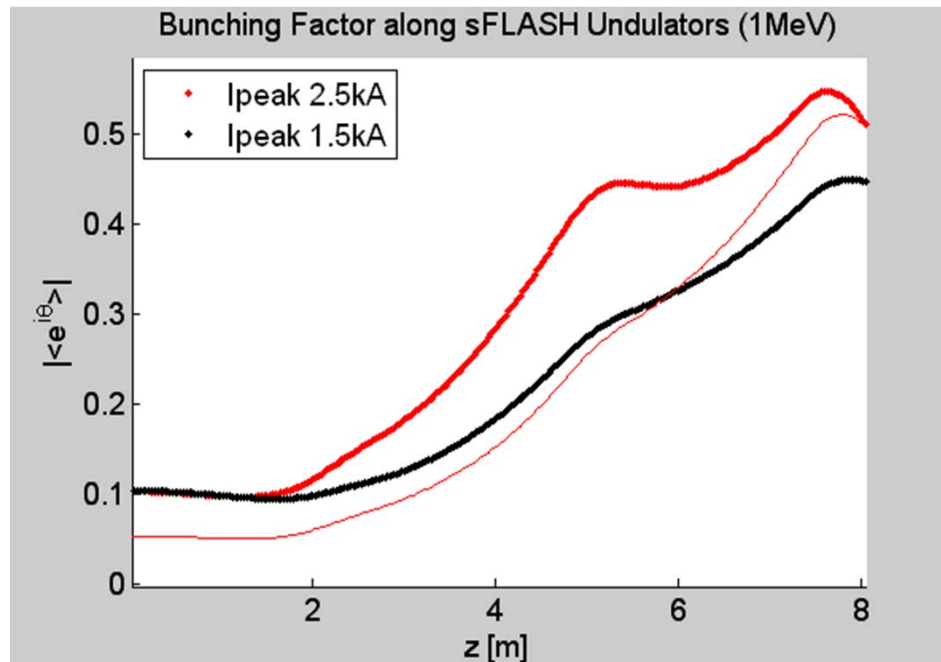
—	$I_{\text{peak}}=2.5 \text{ kA}$	$\sigma_E=250 \text{ keV (rms)}$	bunching=0.05
—	$I_{\text{peak}}=2.5 \text{ kA}$	$\sigma_E=1000 \text{ keV (rms)}$	bunching=0.05
—	$I_{\text{peak}}=2.5 \text{ kA}$	$\sigma_E=2000 \text{ keV (rms)}$	bunching=0.05
⋯	$I_{\text{peak}}=2.5 \text{ kA}$	$\sigma_E=250 \text{ keV (rms)}$	bunching=0.10
⋯	$I_{\text{peak}}=2.5 \text{ kA}$	$\sigma_E=1000 \text{ keV (rms)}$	bunching=0.10
⋯	$I_{\text{peak}}=2.5 \text{ kA}$	$\sigma_E=2000 \text{ keV (rms)}$	bunching=0.10



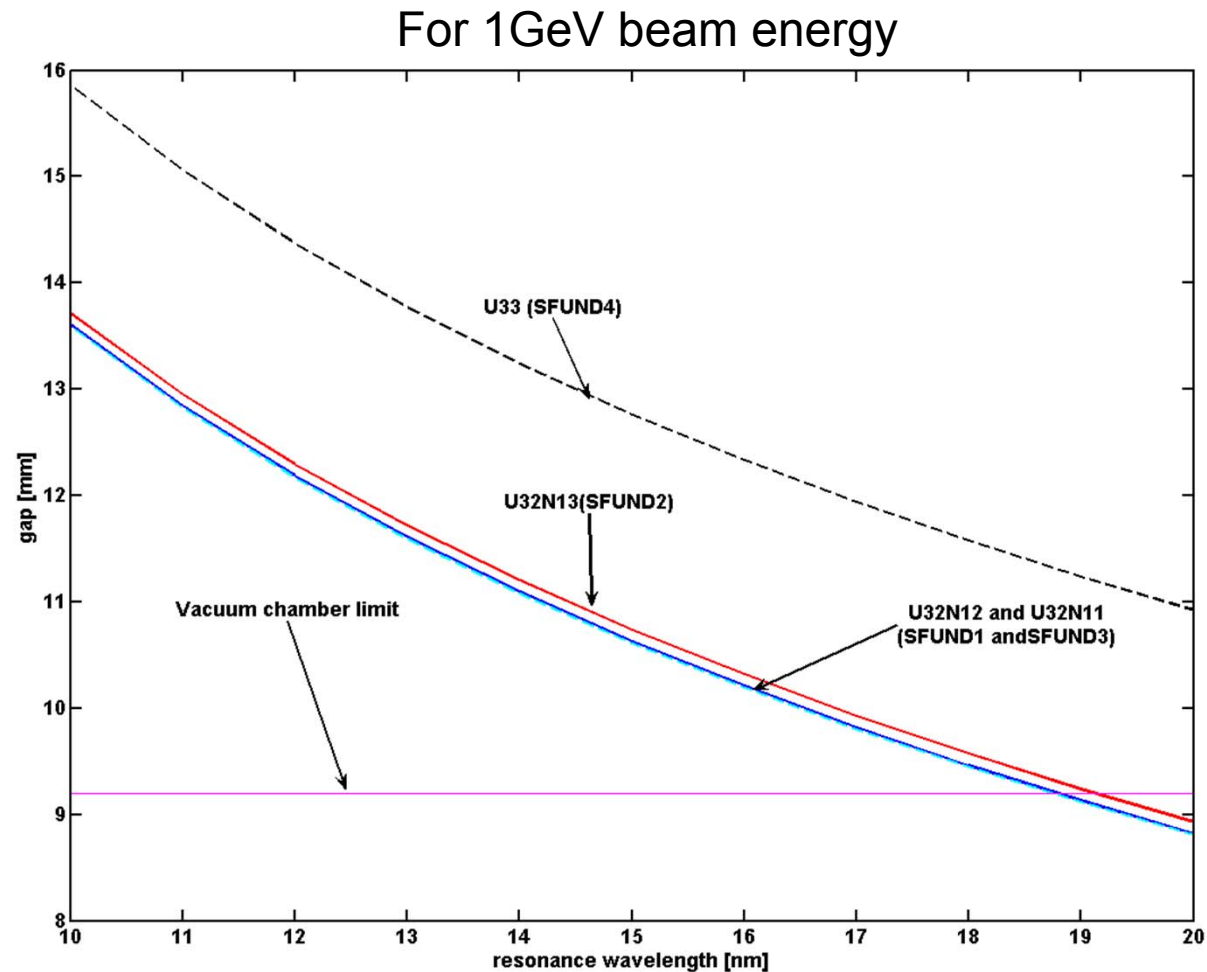
GENESIS

Through the first 3 sFLASH undulators

— (red)	$I_{\text{peak}}=2.5 \text{ kA}$	$\sigma_E=1000 \text{ keV (rms)}$	bunching=0.05
— (black)	$I_{\text{peak}}=1.5 \text{ kA}$	$\sigma_E=1000 \text{ keV (rms)}$	bunching=0.05
- - - (red)	$I_{\text{peak}}=2.5 \text{ kA}$	$\sigma_E=1000 \text{ keV (rms)}$	bunching=0.10
- - - (black)	$I_{\text{peak}}=1.5 \text{ kA}$	$\sigma_E=1000 \text{ keV (rms)}$	bunching=0.10



EEHG with sFLASH undulators



Plot courtesy of Delsim-Hashimi